

IRSP2023

Solid-phase bonding process using nanostructured surface for power devices in automotive

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Resent trends

in Micro Joining Process and Interconnection

Temperature of joint in operation



High-temperature bonding becomes a key technology



Electronic devices on vehicle

Electronic Control Unit is one of the most important electronic devices



ECU: Electronic Control Unit for engine, brake, wiper

More than 20 years ago, vehicles were mostly seen as mechanical systems

Automotive Innovation Driven by Electronics



Source: https://autotecndrive.com/electronic-control-unit/

Expected global market of power devices

2021-2027 total discrete and module market development by end market

(Source: Status of the Power Electronics Industry 2022, Yole Intelligence, August 2022)



0¹⁹⁷² 2022 th

JWRI , Osaka University



Power device packaging

Power device packaging for the automobile electronics



Pb-free joining method for the high temperature application in the literature

Joining method	
High temperature soldering	 Zn-based alloy
	• Au-based alloy
	• Bi-based alloy
Transient liquid phase bonding (TLP)	
Bonding using nanomaterials	Metal nanoparticles



Homologous temperature of alloys and metals





Size effect on melting temperature of Au particles



Ph. Buffat and J-P Borel: Size effect of the melting temperature of gold particles, *Phys. Rev. A*, Vol. 13 (1976), 2287-2298



Behavior of ultrafine gold particles

Change of morphologies and internal structures of ultrafine gold particles



Constantly changed approximately every few tenths of a second

S. lijima and T. Ichihashi: Structural Instability of Ultrafine Particles of Metals, *Phys. Rev. Lett.*, Vol. 56 (1986), 616-619.

Liquid-like behavior of Au grain boundary



G. Casillas, A. Ponce, J. Jesús V.-Salazar and M. José-Yacamán: Direct observation of liquidlike behavior of a single Au grain boundary, Nanoscale, Vol. 5 (2013), 6333-6337.





Bonding process using nanoparticles

Nanoparticle paste

- $\checkmark\,$ High specific surface area \rightarrow low temperature bonding
- ✓ Solvent and organic substances are required
- ✓ Residual organic materials → unexpected large void / gap volume change

New bonding materials proposed from our lab.

- ✓ Stable state
- $\checkmark\,$ Removal or minimum amount of solvent and organic substance
- ✓ High specific surface area like nanoparticle
- ✓ Low-temperature solid-phase bonding



E. Ide et al., *Acta Mater.*, **53** (2005) 2385



Nanoporous metal

Smart Green Processing , JWRI , Osaka University



Dealloying as Nano-processing tool of metals





Formation process of nanoporous by dealloying

·Selectively dissolving Ag from an Ag-Au solid solution via controlled corrosion

Ag dissolution and Au surface diffusion

By Kinetic Monte Carlo (KMC) simulation

At 300 K

Ag₇₅Au₂₅ (fcc) 100 × 100 atoms 90 {111} layers thick



Covered by a single atomic monolayer of Au

Curvaturedriven coarsening by surface diffusion

Ag which was exposed at the surface during coarsening has been dissolved

Tobias Krekeler, Anastasia V. Straber, Matthias Graf, Ke Wang, Christian Hartig, Martin Ritter and Jorg Weissmuller: "Silver-rich clusters in nanoporous gold", *Materials Research Letters*, **5** (2017) 314-321



K. Matsunaga, M-S. Kim, H. Nishikawa, M. Saito and J. Mizuno: "Effect of Au nanoporous structure on bonding strength", *Proc. of ICEP-IAAC 2015*, 830-833 (2015)



Proposal and feature of nanoporous bonding (NPB)

We suggest nanoporous bonding (NPB) method, as a die-attach bonding method for the high-temperature electronics packaging.

> without solvent and organic substances to overcome drawbacks of Compression Si Wafer & Heat nanoparticle pastes







- ✓ **Test specimen** : Oxygen-free Cu disk
- ✓ Conditions of NPB process
 - Temperature : 250, 300, or 350 °C
 - Time: 30 min
 - Applied pressure : 20 MPa
 - Atmosphere : N₂





Interface between Cu and Au nanoporous

Dealloying time: 1 h, NPB process: Temp. 350 °C, Time 30 min, Applied pressure 20 MPa, N₂



K. Matsunaga, M-S. Kim, H. Nishikawa, M. Saito and J. Mizuno: "Effect of Au nanoporous structure on bonding strength", *Proc. of ICEP-IAAC 2015*, 830-833 (2015)



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Fabrication of Ag nanoporous sheet

- ✓ fabrication of melt spun Al-20at%Ag precursor (t = 90~100 µm)
- ✓ dealloying with 2M HCl solution at 75 °C for 3 h



The ligament size of about 110 nm of Ag nanoporous sheet was successfully fabricated.



Sample and temperature profile of joining process Test specimen

- Si chip (3 mm x 3 mm) with backside metallization of Ti/Ni/Au
- active metal brazed Cu Si₃N₄ substrate with ENIG surface finish

✓ Conditions of joining process

- temperature : 300 °C
- applied pressure : 20 MPa
- atmosphere : N₂







Temperature cycling conditions



- Temperature cycling test according to JEDEC standard (JESD22-A104E)
- Temperature fluctuation from
 -55 ° C to 150 ° C
- Soaking time at T_{max} and T_{min}
 10 min
- Heating and Cooling rate 15 ° C/min
- Number of cycles up to 1500 cycles



Change of shear strength of Ag NPB after TC



- Ag/Si mixed
- Si/metallization mixed
- * Ag/Si/metallization mixed

- InitIal shear strength
 22 MPa
- Ag layer
- Ag/Si mixed
- Ag/Si/metallization mixed
 Show comparatively higher values
- Metallization dominant
- Si/metallization mixed
 - Show comparatively lower values



Formation of Cu nanoporous sheet



S. Koga, H. Nishikawa, M. Saito, J. Mizuno: Fabrication of Nanoporous Cu Sheet and Application to Bonding for High-Temperature Applications, *J. Electronic Materials*, **49** (2020), 2151-2158.





B. Park, D-L. Han, M. Saito, J. Mizuno, H. Nishikawa: Fabrication and characterization of nanoporous copper through chemical dealloying of cold-rolled Mn–Cu alloy, *J. porous materials*, 28 (2021), 1823-1836



Grain growth of Cu nanoporous structure during heating

Precursor • Mn–30 at.%Cu (Thickness: 100 µm) • 4% HCl • With annealing

Hearting test10 minN₂ atmosphere



B. Park, D-L. Han, M. Saito, J. Mizuno, H. Nishikawa: Effect of various parameters on the shear strength of solid-state nanoporous Cu bonding in Cu–Cu disks for power device packaging, *J. Electronic Materials*, 51 (2022), 3851-3862.



Shear strength of joints using Cu nanoporous sheet



B. Park, D-L. Han, M. Saito, J. Mizuno, H. Nishikawa: Effect of various parameters on the shear strength of solid-state nanoporous Cu bonding in Cu–Cu disks for power device packaging, *J. Electronic Materials*, 51 (2022), 3851-3862.



B. Park, D-L. Han, M. Saito, J. Mizuno, H. Nishikawa: Effect of various parameters on the shear strength of solid-state nanoporous Cu bonding in Cu–Cu disks for power device packaging, *J. Electronic Materials*, 51 (2022), 3851-3862.

Summary

To establish bonding materials and processes as a low-temperature solidphase bonding technology, a feasibility study has been conducted to determine whether a nanoporous sheet can be used as an insert material.

- ✓ There was an interesting effect of nanoporous-structure generated by the dealloying process on the sintering property of the sheet.
- ✓ The Cu-to-Cu disc joint using the Au nanoporous sheet made with a dealloying time of 1 h at 25 °C had the highest shear strength over 30 MPa in the case of bonding temperature at 350 °C.
- ✓ The Cu-to-Cu disc joint using the Cu nanoporous sheet had the shear strength over 30 MPa under formic acid atmosphere.

Joints using the nanoporous sheet can be achieved with sufficient joint strength and this NPB method is expected to be an alternative to high-Pb-containing solder